# Characterization of 19.9% Efficient CIGS Absorbe

Ingrid Repins, Miguel Contreras, Manuel Romero, Yanfa Yan, Wya Metzger, Jian Li, Steve Johnston, Brian Egaas, Clay DeHart, John Scharf; *National Renewable Energy Laboratory* Brian E. McCandless; *Institute for Energy Conversion* Rommel Noufi; *Solopower* 



This work was supported by the U.S. Department of Energy under Contract No. DE-AC36-99GO10337 with the National Renewable Energy Laboratory.

Thanks to: Craig L. Perkins, Bobby To, Device Performance Group, Falah Hasoon, Tim Gessert, and Ramesh Dhere of NREL.

#### NREL/PR-520-43247

Presented at the 33rd IEEE Photovoltaic Specialist Conference held May 11-16, 2008 in San Diego, California

A national laboratory of the U.S. Depart provided by UNT Office of Energy Efficiency & Ren UNT

Energy Energy

1



National Renewable Energy Laboratory
Innovation for Our Energy Future

Device	Area	Efficiency	Voc	J <sub>sc</sub>	Ff	R	Α	J <sub>0</sub>
	$(\mathrm{cm}^2)$	(%)	(mV)	$(mA/cm^2)$	(%)	$(\Omega-cm^2)$		$(mA/cm^2)$
C1068-2	0.450	18.8	678	35.2	78.7	0.41	1.30	5.3 x 10 <sup>-8</sup>
S2051-A1	0.408	19.2	689	35.7	78.1	0.27	1.48	5.2 x 10 <sup>-7</sup>
C1675-11	0.406	19.3	668	36.2	79.6	0.14	1.29	6.5 x 10 <sup>-8</sup>
C1812-11	0.409	19.5	692	35.2	79.9	0.24	1.33	6.4 x 10 <sup>-8</sup>
M2992-11	0.419	19.9	690	35.5	81.2	0.37	1.14	<b>2.1 x 10<sup>-9</sup></b>

• 19.9% CIGS devices with improved fill factor, reduced recombination

•See Repins et al. Progress in Photovoltaics 16, 2008





Device Name	Area (cm <sup>2</sup> )	η (%)	Voc (mV)	FF (%)	Jsc (mA/ cm <sup>2</sup> )	Official Mst?
M2992-11#5	0.419	19.9	690	81.2	35.4	Yes
C2183-12#5	0.416	19.9	697	80.0	35.7	Yes
C2219-21#7	0.417	19.8	714	79.1	35.1	Yes
M2992-11#4	0.419	19.7	690	81.2	35.1	Yes
M2992-11#6	0.419	19.7	690	81.1	35.3	Yes
C2183-12#4	0.417	19.7	695	80.0	35.5	Yes
C2200-22#1	0.420	19.6	725	80.6	33.6	No
C2213-22#2	0.994	19.2	716	80.4	33.4	Yes

- Processing change: terminate three-stage CIGS deposition without Ga
- •Improved device performance demonstrated in two different evaporators and by three different operators
- •Why does this processing change improve device performance?



- Characterization:
  - Scanning tunneling luminescence (STL) mapping and cathodoluminescence (CL) mapping
  - Transmission electron microscopy (TEM)
  - Time-resolved photoluminescence (TRPL)
  - Capacitance-voltage (CV)
  - Grazing incidence x-ray diffraction (GIXRD)
- Note which results are typical of high-efficiency (>18%) CIGS, and which results are particular to most recent (>19.5%) CIGS.



# STL and CL mapping

Measure intensity and wavelength of luminesced photons as a function of position



CL: electron beam excitation  $\sim 1 \ \mu m$  penetration depth



STL: excitation confined to top 50 nm or less

### Example: CL intensity as a function of position

**SEM** 



Relatively low non-radiative loss at grain boundaries is typical of >18% devices.

19.9% device

13.0% device



Lack of red shift between CL and STL is unique to 19.9% material

## TEM: Atomic number (Z) contrast



19.5%

19.9%

Decreased indication of nanodomains is unique to 19.9% material



#### TRPL



Relatively long lifetime is consistent with high efficiency and low recombination

Factors other than recombination (charge separation, intensity, fitting algorithm) also influence apparent lifetime. *See Metzger et al, E-MRS, May 2008* 

![](_page_8_Picture_4.jpeg)

CV

![](_page_9_Figure_1.jpeg)

Zero-bias depletion width less than 0.5 mm, doping density approaching  $2 \times 10^{16} \text{ cm}^{-3}$ , consistent with >19% devices.

![](_page_9_Picture_3.jpeg)

#### **GIXRD**

![](_page_10_Figure_1.jpeg)

•Compared three samples

•Narrow peaks are characteristic of high efficiency devices

•Record device has largest peak shift

•Not explained by Ga ratio (0.71 would be required)

•Instead, decreased Cu content near surface is implied.

![](_page_10_Picture_7.jpeg)

Summary	Consistent with high η (>18%) devices	Unique to recent 19.9% CIGS
Modified process termination		✓
Low nonradiative loss at grain boundaries	✓	
No red shift between CL and STL		✓
Decreased evidence of nanodomains in TEM		✓
Long lifetime (TRPL)	$\checkmark$	
High doping density / short depletion width (CV)	✓	
Larger shift of GIXRD peak to high angle		✓

•Techniques probing into the bulk are consistent with high efficiency devices.

•Shallow probes indicate a more perfect and Cu-poor formation of the nearsurface region.

•Ga segregates preferentially to  $\alpha$ -phase domains, Cu vacancies to  $\beta$ -phase domains (Stanbery et al.) Hypothesis: Denying Ga to surface encourages more perfect formation of Cu-deficient  $\beta$ -phase and thus the buried homojunction.

![](_page_11_Picture_4.jpeg)